

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Jin (nmi) Zhao, et al.
Serial No. Unknown
Filing Date: July 21, 2003
Title: MAINTAINING A REACTOR CHAMBER OF A
CHEMICAL VAPOR DEPOSITION SYSTEM

Mail Stop Patent Application

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

INFORMATION DISCLOSURE STATEMENT

Applicants respectfully request, pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, that the references listed on the attached PTO-1449 form be considered and cited in the examination of the above-identified patent application. Copies of these references are enclosed for the convenience of the Examiner. No representation is made that a search has been made, that these references qualify as prior art or that these references are material to the patentability of the present application.

Respectfully submitted,

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Date: July 21, 2003

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PTO-1449 Information Disclosure Citation In an Application	Application No. Unknown		Applicant(s) Jin (nmi) Zhao, et al.	
	Docket Number TI-35855 (032350.B505)	Group Art Unit Unknown	Filing Date July 21, 2003	

U.S. PATENT DOCUMENTS

		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	A						
	B						
	C						
	D						
	E						
	F						
	G						
	H						
	I						
	J						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	K							
	L							
	M							
	N							

		DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
	O	G. Bruno, et al., " <i>Study of the NF₃ plasma cleaning of reactors for amorphous silicon deposition</i> ," © 1994 American Vacuum Society, J. Vac. Sci. Technol. A 12(3), pages 690-698.	May/June 1994
	P	Srihari Ponnekanti, et al., " <i>Failure mechanisms of anodized aluminum parts used in chemical vapor deposition chambers</i> ," © 1996 American Vacuum Society, J. Vac. Sci. Technol. A 14(3), pages 1127-1131.	May/June 1996
	Q	Hsin-Pai Hsueh, et al., " <i>Ion energy distributions and optical emission spectra in NF₃-based process chamber cleaning plasmas</i> ," © 2001 American Vacuum Society, J. Vac. Sci. Technol. B 19(4), pages 1346-1357.	Jul/Aug 2001
	R		

EXAMINER	DATE CONSIDERED
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.	

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